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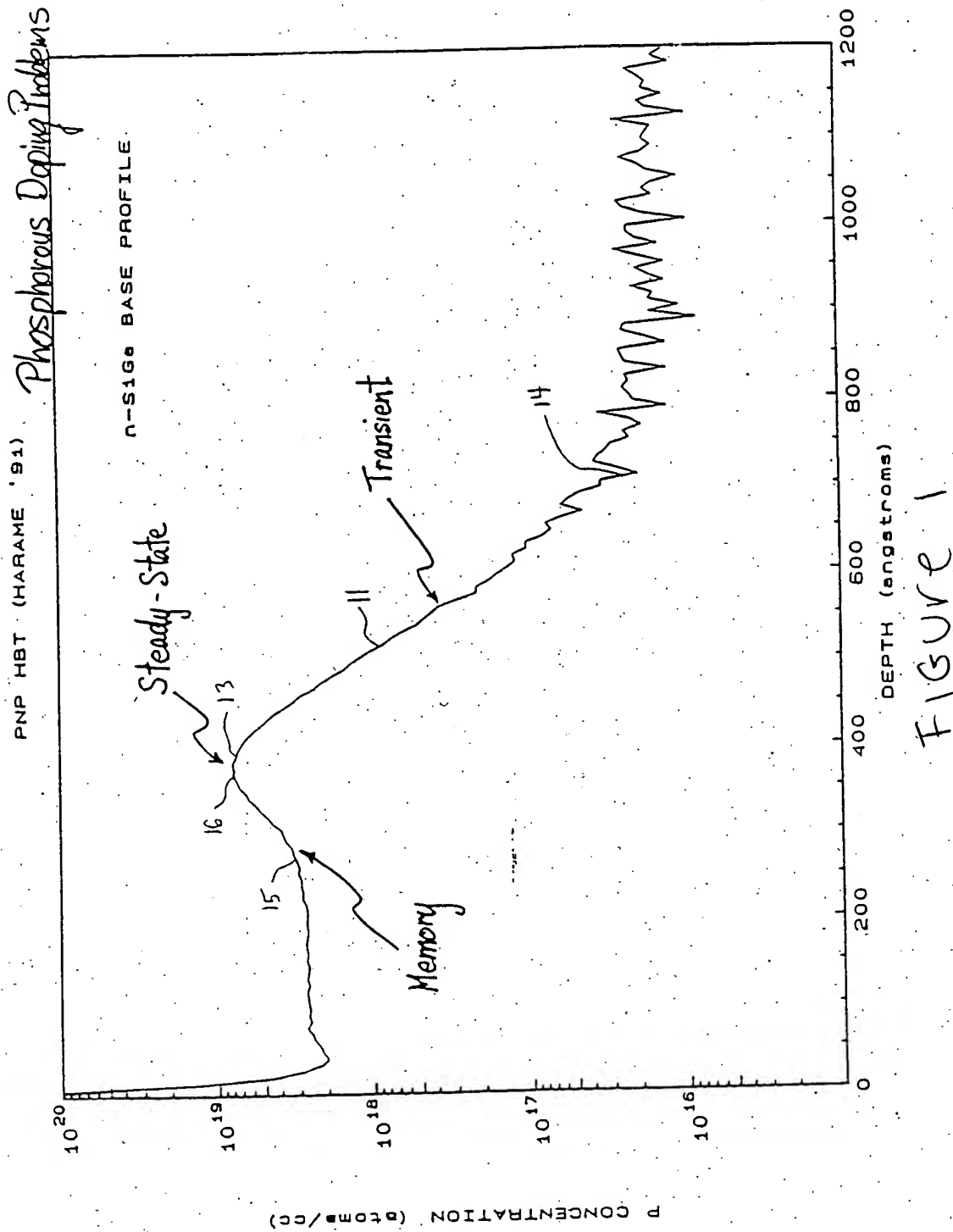
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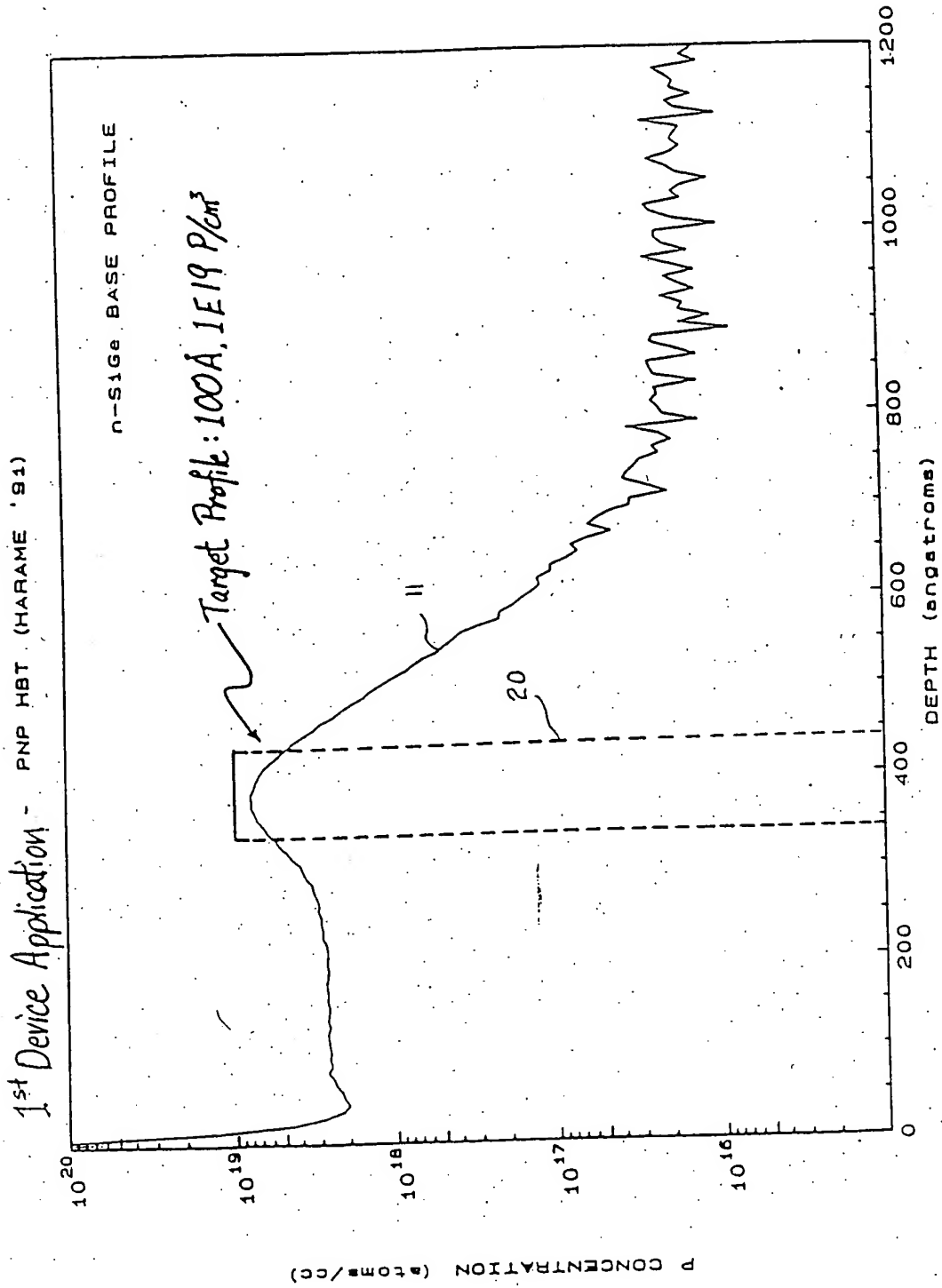


Figure 2

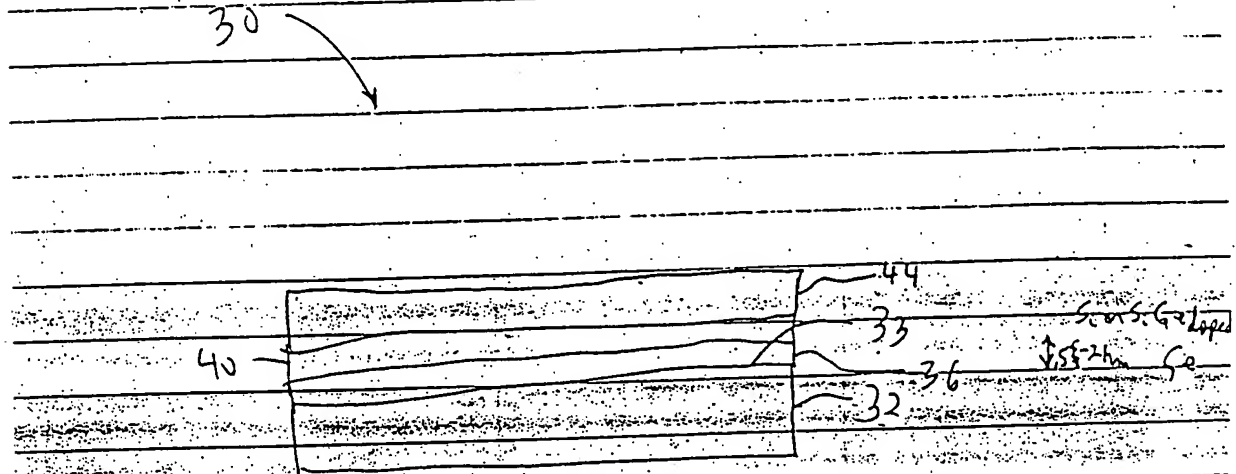


FIGURE 3

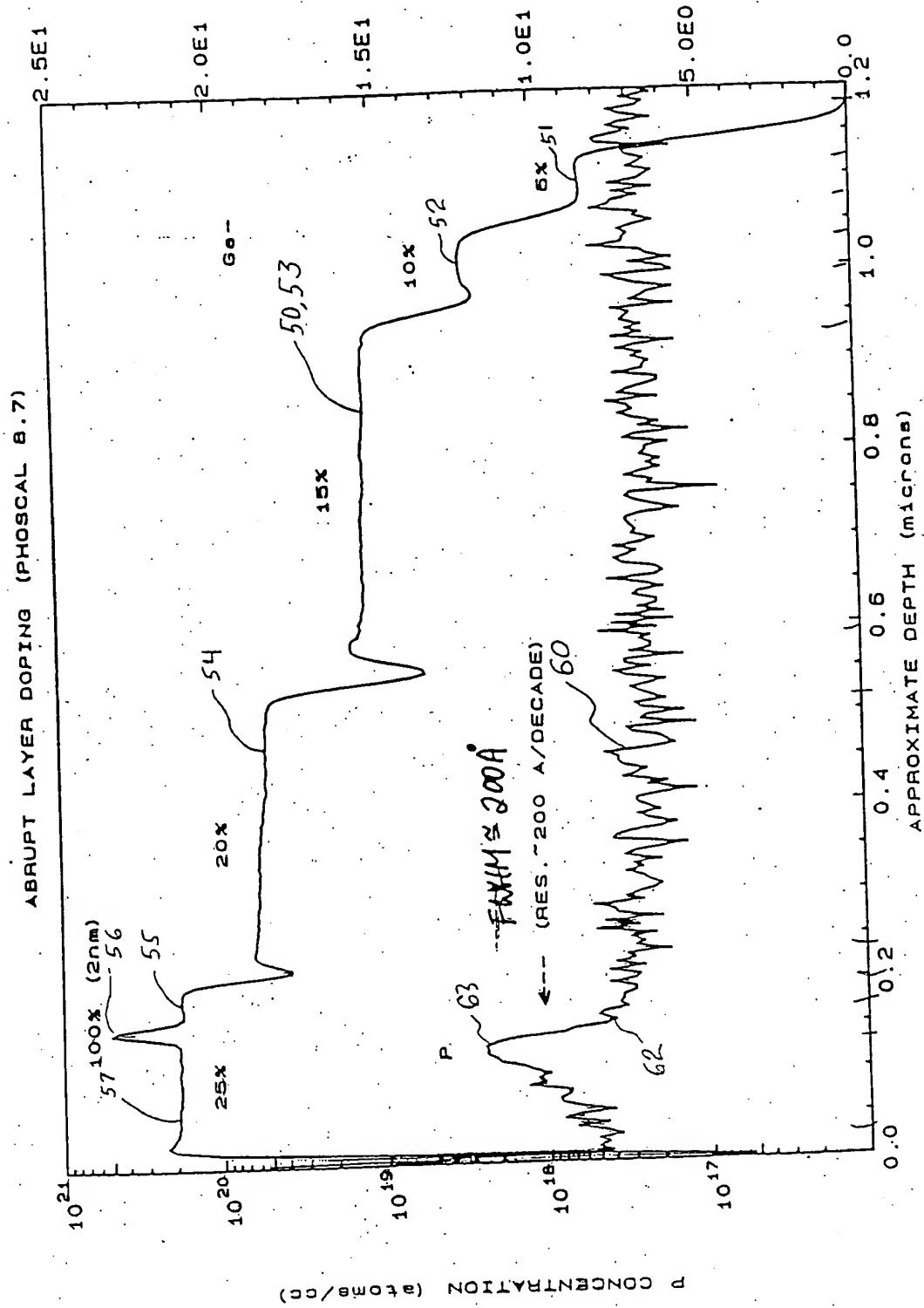
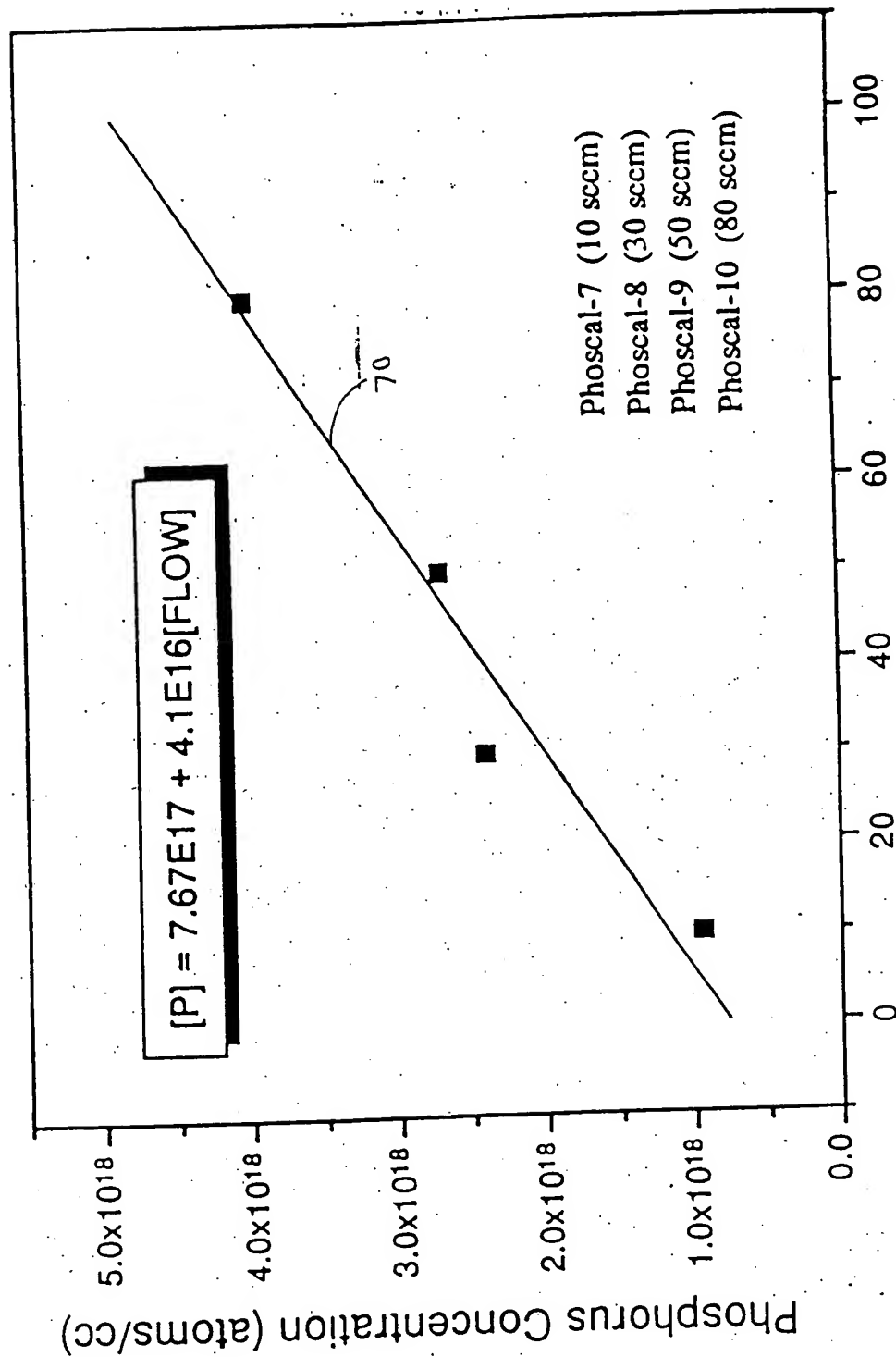


FIGURE 4

# Ge:P Delta Doping Calibration @ 480 C



100 PPM PH<sub>3</sub>/He Mixture Flow (SCCM)

FIGURE 5

## P-doping calibration

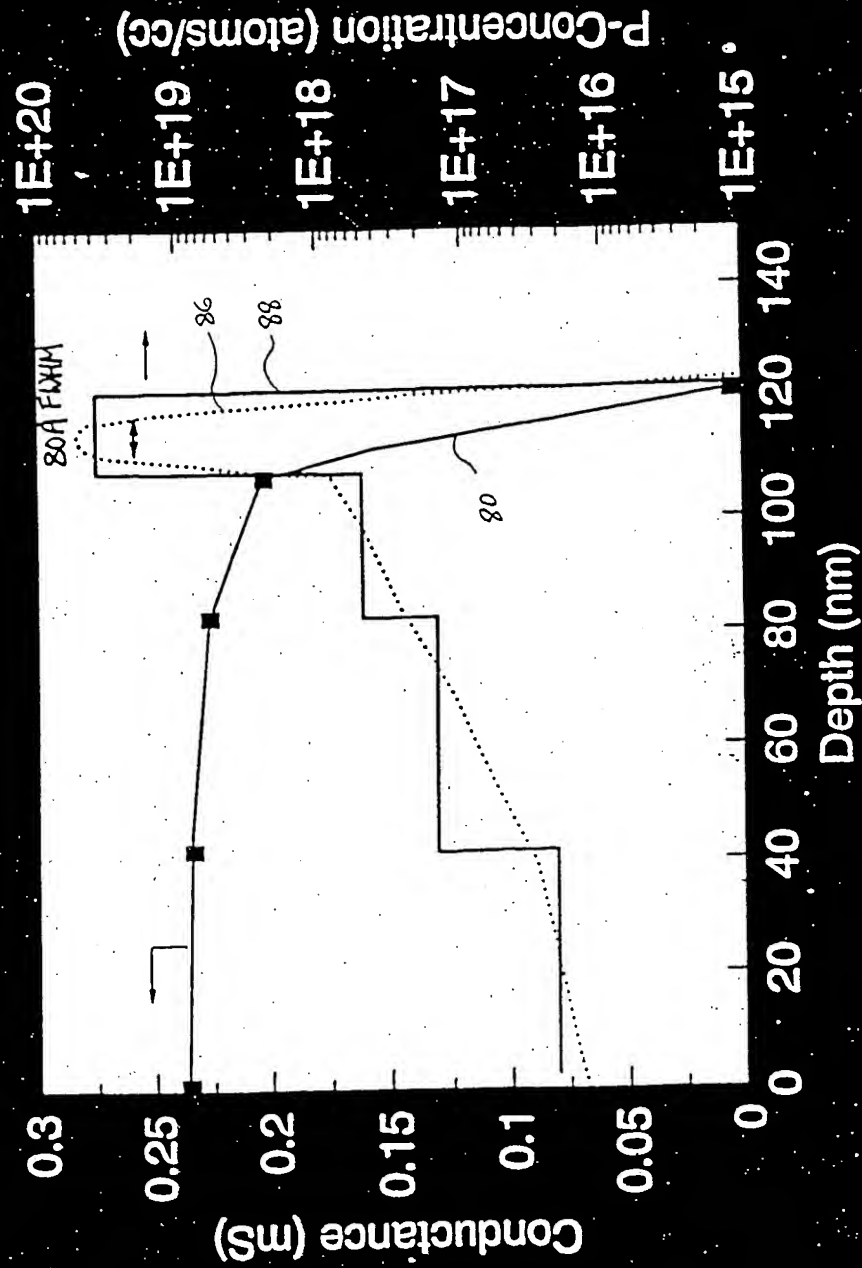


FIGURE 6

~~Application of abrupt implantation  
for channel doping engineering~~ 83

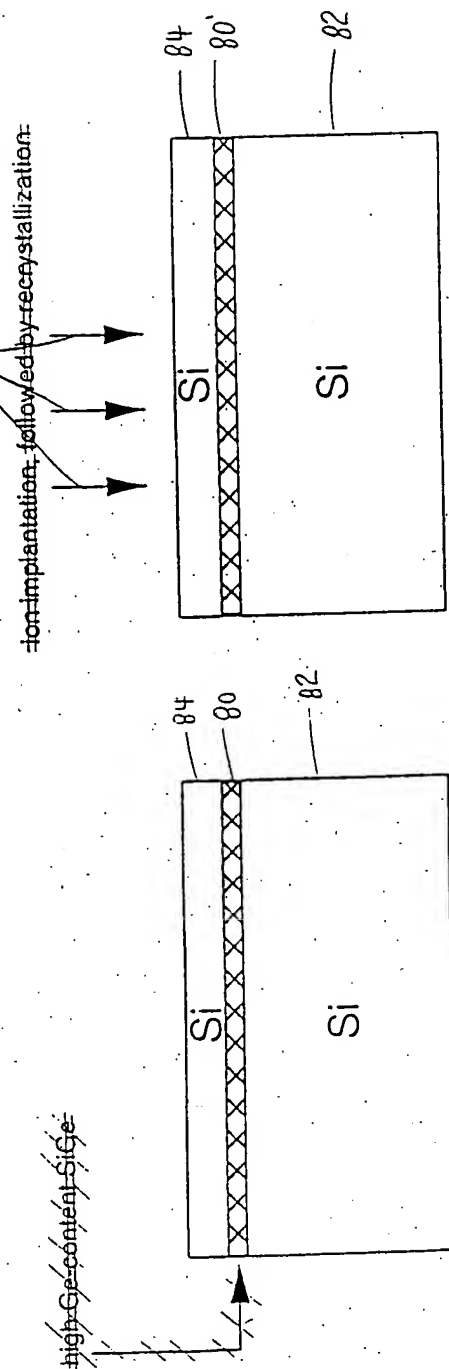


FIGURE 7

FIGURE 8

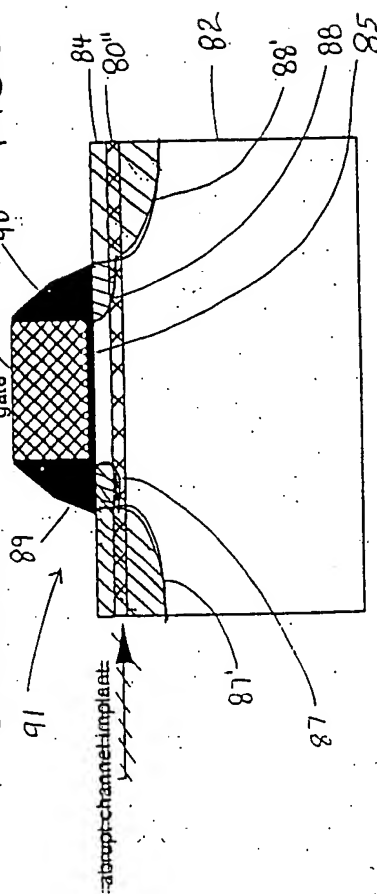


Figure 9.



# Application of abrupt doping in FET design

